

ION BEAM ANALYSIS OF THIN LAYERS

Ion beam analysis (IBA)

Ion beam analysis techniques form a group of powerful methods to analyse the composition and thickness of thin films with thicknesses between sub-monolayer and micron(s). Techniques as RBS, ERD, NRA, PIXE and PIGE provide useful additions to techniques such as SIMS, AES, SEM-EDS, FTIR, XPS, etc. The results are easy to interpret and, in contrast to the results of many other techniques, unambiguously quantifiable.

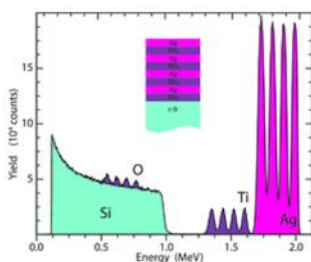
IBA is ideal to determine elemental concentration depth profiles, contaminations and thickness in terms of at/cm² and also the film density when the thickness in nm is known.

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EXAMPLE RBS

A multi-layer consisting of 4 Ag/TiO₂ bilayers on a Si substrate, as measured by RBS. The table below shows the RBS outcome.



layer	thickness 10 ¹⁵ at/cm ²	nm*
Ag (surface)	268	46.2
TiO ₂	369	39.2
Ag	281	48.4
TiO ₂	371	39.4
Ag	281	48.4
TiO ₂	379	40.2
Ag	285	49.1
TiO ₂	399	42.3

*) calculated assuming bulk densities

EXAMPLE ERD

Diffusion of H and D during annealing at 1100°C made visible with ERD:

